

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): George D. Papasouliotis; Bart van Schravendijk; Robert D. Tas; Patrick A. Van Cleemput

Assignee: Novellus Systems, Inc.

Title: Process for Depositing F-Doped Silica Glass in High Aspect Ratio Structures

Serial No.: 10/035,773 Filing Date: December 21, 2001

Examiner: Julian A. Mercado Group Art Unit: 1745

Docket No.: M-5091-2P US

Irvine, California  
July 20, 2004

MAIL STOP AMENDMENT  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

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JUL 20 2004

RESPONSE TO OFFICE ACTION

OFFICIAL

Dear Sir:

In response to the Office Action dated May 13, 2004, please amend the above-identified application as follows.

LAW OFFICES OF  
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